





Some aspects of reactive thermo-chemically non-equilibrium plasmas

G. Tetard, F. Mohasseb, K. Ouaras, A. Allouch, A. Michau, S. Prasanna, J. Mougenot, C. Rond, G. Lombardi, M. Redolfi, X. Duten, F. Benedic, A. Gicquel, K. Hassouni, C. Arnas^{*}, S. Longo^{**}

LSPM, CNRS - UPR 3407 CNRS, Université Sorbonne Paris Nord, Villetaneuse, France *Laboratoire PIIM, CNRS-Aix-Marseille Université, Centre Saitn-Jérôme, Marseille, France **Dipartimento di Chimica, Universita dei Stugli di Bari, Bari, Italia

Overview

- Phenomenological description
- Electron kinetics in non-equilibrium discharges
- Reactivity and kinetics of electronically excited states- consequence on ionization kinetics and plasma characteristics : the example of hydrogen
- Vibrational kinetics and its impact on molecular dissociation : the example of molecular nitrogen
- Molecular growth, i.e., "plasma polymerization" in non equilibrium discharges :
 - Sputtering DC discharges with graphite electrodes
 - Ar/C₂H₂ capacitively coupled RF discharges
- Interplay between power coupling, energy relaxation, chemistry, and transport in reactive plasma
 - H_2/CH_4 microwave cavity plasmas
 - Ar/C₂H₂ capacitively coupled RF discharges
- Few slides on the methodology



Few words on laboratory plasmas : a phenomenological description

Plasma-wave interaction Electron heating

Electron-heavy species collisions Energy transfer, ionisation, etc

Collisions between heavy species Energy transfer, chemistry, clustering,

charged particle transport : Drift, Diffusion, convection Energy and mass transport plasma/surface Interaction

Energy and mass transfer



Substrate (T_s, c_s)



Energy and mass

transfer

e+AB

'AB(v), AB(r), AB'

AB+, A, B, B+, A

Few words on laboratory plasmas: different types of chemical species and practical interest

Gas phase generated species in laboratory plasmas



Gas phase reactions :

- → Atomic/molecular species : O-atom, F-atom, H-atom
- → Radicals : CH_3 , CF_3 , SiH_2 , SiH, SiH_3
- → Positive ions : CH_5^{+} , SiH_5^{+} , H_2^{+} , H_3^{+} , H^+ , O_4^{+} , etc.
- \rightarrow Negative ions : H⁻, O⁻
- → Large molecular structures : $S_nH_m^-$, $C_nH_m^-$, etc.
- ➔ Nucleation and growth of solid particles

Plasma processes

- Surface treatment
- Material deposition
- Chemical synthesis/decomposition
- Particle/nanostructure nucleation
- Active species/photons /fast particles sources



Few words on Laboratory plasmas Phenomenological description



Electrons are the drivers for the plasma reactivity \rightarrow Electron kinetics



Electron probability density function

Electrons occupy different Probability Density Function in phase space : $f_e(v_e, r_e)$ positions and show different velocity values $f_e(v_e, r_e)dv_edr_e$: number of electrons at positions in the



position range $r_e \pm \frac{dr_e}{2}$ with velocity-values in the range $v_e \pm \frac{dv_e}{2}$



Local electron density

$$n_e(r_e) = \int_{v_e} \frac{d^2 N_e}{dr_e} = \int_{v_e} f_e(v_e, r_e) dv_e$$

Electron states in a plasma : electric field , collisions, transport/boundaries

$$\frac{\partial f_{e}}{\partial t} + \vec{v}_{e} \cdot \vec{\nabla} f_{e} - \frac{e}{m} \vec{E} \cdot \vec{\nabla}_{v} f_{e} = C(f_{e})$$



Collision frequency and rate constant

e-HS Collisions : Local and instantaneous



Collision frequency for 1 e⁻ in s⁻¹: $v_c(v_e) = \sigma_c(v_e)v_e n_{HS}$

A collision is characterized by an integral collision cross section $\sigma_{c}(v_{e})$ in cm

For the whole electron population the collision frequency per unit volume s⁻¹cm⁻³:

$$\overline{v}_{c} = \int_{v_{e}} f(v_{e}) dv_{e} v_{e} \sigma_{e} n_{tot} = k_{c} n_{e} n_{tot}$$

Also define the rate constant

$$K_{c} = \frac{\int\limits_{v_{e}} f(v_{e}) dv_{e} v_{e} \sigma_{e}}{\int\limits_{v_{e}} f(v_{e}) dv_{e}}$$

$$\int_{v_e} \boldsymbol{f}(\boldsymbol{v_e}) dv_e = n_e$$



Different types of Electron/heavy species Collisions

Elastic: => e-HS Momentum and kinetic energy transfer (electron current and direct gas heating): $e^{-}(v_e) + A_2(v_{HS}) => e^{-}(v'_e) + A_2(v'_{HS})$ Total kinetic energy (e+HS) conserved

Inelastic non-reactive => Excitation/de-excitation of the electronic, vibrational or rotational modes and electron cooling(superelastic)



Different types of Electron/heavy species Collisions

Reactive inelastic → Ionization, dissociation, dissociative attachment

- $e^{-}(v_e) + A_2(Y,v,J) \rightarrow [A_2(Y^{diss},v',J')] \rightarrow e^{-}(v'_e) + 2A$
- $e^{-}(v_e) + A_2(Y,v,J) \rightarrow e^{-}(v_e) + e^{-}(v_e) + A_2^{+}(Y',v',j')$
- $e^{-}(v_e) + A_2(Y,v,J) \rightarrow [A_2^{+}(Y^{diss},v',j')] \rightarrow e^{-}(v'_e) + e^{-}(v''_e) + A + A^{+}$

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e^{-}(v_e) + A_2(Y,v,J) => A + A^{-}
```

Super-elastic (inelastic reverse process) → internal mode de-excitation and electron heating)

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e^{-}(v_e) + A_2(Y',v',J') => e^{-}(v'_e) + A_2(Y,v,J)
```



Cross section trends, collision frequency and energy transfer rate



Collision frequency $v_c(v_e) = \sigma_c(v_e)v_e n_{HS}$

Elastic >> **In_vib** ≥ **Ine_other**

Energy transfer rate: Elastic: $v_{E-el}(v_e) \propto \sigma_c(v_e) v_e n_{HS} \frac{m_e}{m_{HS}} \varepsilon_e$

Inelastic: $v_{E-In}(v_e) \propto \sigma_c(v_e) v_e n_{HS} \varepsilon_{th}$

In_vib >=< Ine_other >> El



E-HS rate constant and electron PDF

Major questions when investigating reactive non equilibrium plasmas for a population of electrons :

1/ What are the rates of the primary e-HS collisions $r_{e-HS} = k_{e-HS}n_en_{HS}$ that sustain the plasma and generate the primary $r_{e-HS} = k_{e-HS}n_en_{HS}$

2/ What are the rates and the main channels for electron energy dissipation in the gas (self-consistent model) ? ? $k_{e-HS}(r_e) = \int f(r_e, v_e) \sigma_{e-HS}(v_e) v_e dv_e$ Electron energy dissipation $r_{e-HS}^e = k_{e-HS} n_e n_{HS} \varepsilon_{th}$ Boltzmann equation

$$\int_{v_e} \frac{\partial f_e}{\partial t} + \vec{v}_e \cdot \vec{\nabla} f_e - \frac{e}{m_e} \vec{E} \cdot \vec{\nabla}_{v_e} f_e = C(f_e)$$

• Three major practical situations :

1- No assumption : Solve the Boltzmann in the full phase space. Suitable for low density plasma, i.e., $n_e < 10^{12} - 10^{13}$ cm⁻³ – no electron-electron collisions. Necessary when non local and anomalous effects (anisotropy, fluctuation, beam-like, etc.) are important : sheaths, magnetized plasmas, etc

2- Assume that the PDF is local (2a) and isotropic(2b) : develop the PDF as a LC of spherical harmonic functions and keep either only the isotropic component (classical/old) or the isotropic + the first anisotropy (newer see Hageaar and Pitchford PSST) : suitable for most of the reactive plasmas.

3- Assume a local Maxwellian PDF suitable for large density-low pressure plasmas (enhanced electron-electron collisions → Maxwell distribution)

$$f_e(v_e) = \left(\frac{m_e}{2\pi kT_e}\right)^{\frac{3}{2}} exp\left(-\frac{m_e v_e^2}{2kT_e}\right)$$



Illustration case 1 : statistical particle simulation Electron dynamics and Particle In Cell simulation



Illustration case 1: statistical particle simulation e-HS collisions and Monte Carlo approach





Illustration case 1: Capacitively coupled RF discharge in N₂





Stochastic heating at the sheath edge → Bi-Maxwellian EEDF

- \rightarrow Large temperature 3 eV for high energy electrons
- \rightarrow Low temperature, 0.5 eV, for low energy electrons

 $k_{n-max}/k_{max} > 10^2$

S. Longo, K. Hassouni, D. Iasillo and M. Capitelli, J. Phys. III, Fr, 7 (1997) 707-718 DOI: 10.1051/jp3:1997133
S. Longo, M. Capitelli and K. Hassouni, . *Phys. IV France 07 (1997) C4-271-C4-281DOI*: 10.1051/jp4:1997422



Illustration case 1 : electron kinetics in argon DC discharge (Monte Carlo)



A. Michau et al. PISST, **25**, (2016), paper# 015019(16 pp) doi:10.1088/0963-0252/25/1/015019Pl



Illustration case 2 : electron kinetics in moderate pressure H_2/CH_4 plasmas





What about electric-field modulation (E=E₀cos($\omega_{HF}t$)? =>electron may follow the field depending on v_{e-ex}/ω_{HF} => 2 options

1- Low pressure case : $\frac{m_e}{m} \nu_{el} + \nu_{in} \ll \omega_{HF}$ **+** stationary situation **+** Use the effective field assumption

$$E_{\text{eff}} = \frac{E_0}{\sqrt{2}} \frac{v_m^e}{\left(v_m^{e^2} + \omega^2\right)^{1/2}}$$

2- high pressure case : $\frac{m_e}{m} v_{el} + v_{in} \gg \omega_{HF}$ \Rightarrow non-stationary situation for electrons \Rightarrow time-integrate the BE

EEDF behavior in collisional high frequency plasmas



Bimodal stationary distribution

EEDF Bimodal Te-h = f(Te-l) (univoque) Energy balance → Te-l

K. Hassouni et al. PSST 8(1999), 494-512

- K. Hassouni et al. Surf. Coat. Technol. **97**(1-3), 391-403 (1997)
- M. Capitelli et al. Plasma Chem. And Plasma Proc. 16, pages 153–171 (1996)



Impact of the effective field assumption

Low pressure case

High pressure case



Effective field assumption and non stationary model give almost the same result

M. Capitelli et al. Phys. Rev. E 1843 (1996)

W. Morscheidt et al. Plasma Chem. Plasma Proc. 23, 117-140, (2003) doi: 10.1023/A:1022472904111



Discharge maintenance : Ionization kinetics

In principle : the most straightforward mechanism \rightarrow direct ionization :



But less straightforward mechanism may exist : multi-step

- Penning

$$e_{h}^{-} + A \rightarrow A^{(**)} + e_{h-th}^{-}$$
$$A^{(**)} + B \rightarrow A^{(*)} + B^{+} + e^{-}$$

- step-wise

$$e_h^- + A \rightarrow A^{(*)} + e_{h-th}^-$$
$$e^- + A^{(*)} \rightarrow A^+ + 2e^-$$



Stepwise and Penning mechanism illustration : The coupling between electronic and ionization kinetics in H_2 plasmas

Chemical species : H₂ and H

Direct lonization: $e^- + H_2 \rightarrow H_2^+ + 2e^-$ and $e^- + H \rightarrow H^+ + 2e^-$

Closer look

- Electronic excitation of : H₂ and H
- $e^{-} + H_2 ==> e^{-} + H_2^*$
- $e^{-} + H(n) ==> e^{-} + H(m)$
- Stepwise ionization involving electronically excited states
- $e^{-} + H_2 = [H_2^{**}] => H_2^{+} + 2e^{-}$
- $e^{-} + H(n) = 2e^{-} + H^{+}$
- Penning ionization through H-atom excited state :
- $H(n) + H_2 = [H_3^+ + e^-] \text{ ou } [3H]$

- Need to look at collisional and radiative relaxation processes

- $H_2^* (+M) ==> H_2^{**} \text{ or } 2H (+M)$
- H(n) + H => H(m) + H
- M* ==> M*' + hv (M=H or H₂)



H₂ Microwave plasmas Microwave cavity coupling Pressure : few tens of mbars



Stepwise and Penning mechanisms illustration : The coupling between electronic and ionization kinetics in H_2 plasmas





Ionization is mainly governed by H(n=2-3) quenching

K. Hassouni et al. PSST **8**(1999), 494-512

K. Hassouni et al. Surf. Coat. Technol. **97**(1-3), 391-403 (1997)



Penning vs stepwise vs direct ionization mechanisms : the example of CCRF Ar/C_2H_2





Primary activation processes : the coupling between molecular dissociation and vibrational kinetics in N_2 plasmas

What's the main dissociation mechanism in the plasma bulk :

e-v excitation processes

$$e^{-} + N_2 (v) \leq e^{-} + N_2(w)$$

Resonant v-v relaxation processes
 $N_2(w) + N_2 (v) \leq N_2(v-1) + N_2(w+1)$
V-t de-excitation process
 $M + N_2 (v) \leq N + N_2(v-1)$
K. Hassouni et al. (

$$\begin{split} &M + N_2 (v_{\acute{e}lev\acute{e}}) <=> M + 2N \\ &N_2 (v_{\acute{e}lev\acute{e}}) + N_2 (v) <=> N_2 (v-1) + 2N \end{split}$$

K. Hassouni et al. Computer and Chem. Eng. (1993), **17**(Supp. 1), S505-S510 S. Longo et al. , J. Phys. III, Fr, **7** (1997) 707-718 DOI: 10.1051/jp3:1997133 S. Longo et al. . *Phys. IV France* **07** (1997) *C4-271-C4-281*DOI: 10.1051/jp4:1997422



RF

Nitrogen

Primary activation processes : the coupling between molecular dissociation and vibrational kinetics in N_2 plasmas



 $e^{-} + N_2(v=0) = e^{-} + N_2(v=1-4)$

pompage sur les bas niveaux



 $N_2(v) + N_2(w) = N_2(v-1) + N_2(w+1)$

Montée dans l'échelle vibrationnelle

 $N_2(vl) + N_2(v)$ (ou M) => 2N + $N_2(v-1)$ (ou M)

Dissociation du dernier niveau par collision avec un lourd





Self-limiting effects for the vibrational dissociation mechanism in N_2 plasmas





Attachment and molecular growth kinetics in non equilibrium plasmas : the case of sputtering DC discharges



Dusts are produced by the sputtering of the graphite cathode:

- Argon ions accelerated in the sheath
- Fast neutrals resulting from charge transfer Ar_{slow} + Ar⁺ → Ar⁺ + Ar_{fast}

What is the mechanism responsible for dust formation ?



Attachment and molecular growth kinetics in non equilibrium plasmas : the case of sputtering DC discharges





Attachment and molecular growth kinetics in non equilibrium plasmas : Confining effect of field reversal in DC discharges

Three electron populations: fast (ionizing), intermediate (energy below the first excitation threshold), cold (trapped in the field reversal)



Attachment and molecular growth kinetics in non equilibrium plasmas : field reversal and molecular growth in DC discharges



Field-reversal at 2 cm from the cathode.

→ Electrostatic trapping of negative species is possible

sputtered C, C₂, C₃ induce a molecular growth : $C_{x=1-3} + C_{x'=1-3} \rightarrow C_{x+x'}$ $C_n + e^- \rightarrow C_n^- \ (n \ge 4) + h\nu$ radiative attachment $C_n^- + C_x \rightarrow C_{n+x}^- \ (n \ge 4)$ growth Nucleation rate



A. Michau et al. Plasma Chem. And Plasma Proc., 32, 451-470(2012). Doi : 10.1007/s11090-012-9357-0
A. Michau et al. PSST, 25, (2016), paper# 015019(16 pp) doi:10.1088/0963-0252/25/1/015019Pl
A. Michau et al. PSST (2010) paper , 034023(7pp) doi 10.1088/0963-0252/19/3/034023



Negatively charged clusters



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Attachment and molecular growth kinetics in sputtering DC discharge



Key-role of Field reversal and negatively charged species for molecular growth



Ionization and molecular growth kinetics in Ar/C_2H_2 CCRF plasmas



Answer :

- **RF plasmas fluid model** (G. Tetard et al. PSST (2021), **30**, paper# 105015(22 pp) doi 10.1088/1361-6595/ac2a17) Handle large time-scale chemistry

008) 225201(14 pp))	The growth starts with
k~ 3.10 ⁷ m ³ .mol ⁻¹ .s ⁻¹ k~4.10 ⁷ m ³ .mol ⁻¹ .s ⁻¹	$e^{-} + C_2H_2 \rightarrow e^{-} + C_2H + H$
k~6.10 ⁵ m ³ .mol ⁻¹ .s ⁻¹	$e^- + C_2H_2 \rightarrow C_2H^- + H$
:6) k~6.10 ⁷ m ³ .mol ⁻¹ .s ⁻¹	$e^{-} + C_2H_2 \rightarrow C_2H_2^+ + 2e^{-}Or$ Ar* + $C_2H_2 \rightarrow C_2H_2^+ + Ar + e^{-}$
	$ \begin{array}{l} \begin{array}{l} & \text{(14 pp))} \\ & \text{(14 pp)} \\ & (14$



Ionization and molecular growth kinetics in Ar/C_2H_2 CCRF plasmas : discharge structure and composition



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C₂H₂ density in the gap



- Total acetylene conversion at low flow inletvelocity
- Substantial conversion (50%) at large flow velocity
- Substantial production of large molecular edifice at low residence time !

G. Tetard et al. PSST (2021), **30**, paper# 105015(22 pp) doi 10.1088/1361-6595/ac2a17 G. Tetard et al. Submitted to Plasma Process and Polymer - 2021

Ionization and molecular growth kinetics in Ar/C_2H_2 CCRF plasmas : Charge species in the gap



Narrow highly electronegative region in the center of the gap Electropositive plasma elsewhere

G. Tetard et al. PSST (2021), 30, paper# 105015(22 pp) doi 10.1088/1361-6595/ac2a17

G. Tetard et al. Submitted to Plasma Process and Polymer - 2021



Ionization and molecular growth kinetics in Ar/C_2H_2 CCRF plasmas : major molecular growth routes



- Neutral route dominate when C_2H_2 density is low in the gap
- Positive ion route dominate when C_2H_2 density is significant in the gap

G. Tetard et al. Submitted to Plasma Process and Polymer - 2021



Ionization and molecular growth kinetics in Ar/C_2H_2 CCRF plasmas : Molecular growth and nucleation

Size distributions of hydro-carbons

$10 \% C_2 H_2$ in the feed gas



Several orders of magnitude exponential population decrease with size

50 % C_2H_2 in the feed gas



Mass accumulation over all the size distribution (very slight or no decrease)

Only the positive ion route can lead to nucleation ... in this growth model !!!

G. Tetard et al. Submitted to Plasma Process and Polymer - 2021



Competitive processes for molecular growth

 $C_{14}H_2$ $C_{14}H_2$ $C_{12}H_{2}$ Wall Deposition 60% +C₂H $+C_2H_2$ %C2H2=50% 1% $C_{12}H_2$ C₁₂H Convective Wall losses ⊦e- (Ar*) Deposition 92% 6%

Neutral molecule route



Positive ion route



G. Tetard et al. Submitted to Plasma Process and Polymer - 2021

- Convective losses of neutral clusters are highly dominant which explains the limited contribution of this route in the nucleation process
- Significant competition between molecular growth and wall deposition for the neutral route
- Molecular growth is dominant for both negative and positively charged clusters



Complex chemistry and the coupling between thermal, chemical and transport phenomena in hydrocarbon containing microwave plasmas



- 1- Wave-plasma interaction energy deposition
- 2- Electron heating and collisional relaxation
- 3- Gas excitation and heating
- 4- Thermal and electron-impact chemistry
- 5- Composition change





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Plasma composition at low power density-low pressure (9 W/cm³, 2500 Pa)



Moderate temperature increase Electron-impact dissociation of H-atom Non-equilibrium H-atom density

K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp) F Silva et al 2009 J. Phys.: Condens. Matter 21 364202

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Substantial conversion of CH₄ Smooth evolution of the plasma composition Slightly <u>reactive boundary layer</u> Both thermal and electron-impact chemistry

G. Lombardi et al. PSST **14**(2005), 440-450, doi : 10.1088/0963-0252/14/3/005 G. Lombardi et al., J. Appl. Phys. **98**, 053303 (2005); <u>https://doi.org/10.1063/1.2034646</u>

Plasma composition at low power density-low pressure (9 W/cm³, 2500 Pa)



From CH₄ feed to Acetylene plasma **Substantial but still 'smooth' variatio**n of the Composition in the BL

K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp) F Silva et al 2009 J. Phys.: Condens. Matter 21 364202



Dominated by hydrocarbon ions Hydrogen ionization followed by ion conversion processes

 $H(n) + H_2 ==> [H_3^+ + e^-] ou [3H]$ $H_3^+ + C_x H_y
ightarrow C_x H_{y+1}^+ + H_2$

G. Lombardi et al. PSST **14**(2005), 440-450, doi : 10.1088/0963-0252/14/3/005 G. Lombardi et al., J. Appl. Phys. **98**, 053303 (2005); <u>https://doi.org/10.1063/1.2034646</u>



Plasma composition at high power density-high pressure (50 W/cm³, 10000 Pa)



1 carbon species



Large temperature increase Thermal dissociation of H-atom Large dissociation yield Still non-equilibrium H-atom density

K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp) F Silva et al 2009 J. Phys.: Condens. Matter 21 364202 **Full conversion of CH**₄ before reaching the plasma bulk **Highly reactive boundary layer**

G. Lombardi et al. PSST **14**(2005), 440-450, doi : 10.1088/0963-0252/14/3/005 G. Lombardi et al., J. Appl. Phys. **98**, 053303 (2005); <u>https://doi.org/10.1063/1.2034646</u>



Plasma composition at high power density-high pressure (50 W/cm³, 10000 Pa)



Still C_2H_2 plasma ! Very large variation in the BL Driven by H-atom and T_g

H₂ ionization and Charge transfer in the plasma Substantial H-atom ionization Very large and highly ionized post-discharge

G. Lombardi et al. PSST 14(2005), 440-450, doi: 10.1088/0963-0252/14/3/005

G. Lombardi et al., J. Appl. Phys. 98, 053303 (2005); https://doi.org/10.1063/1.2034646

Electron (microwave) \rightarrow T_g \rightarrow H-atom THEN T_g and H-atom \rightarrow hydrocarbon chemistry

K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp) F Silva et al 2009 J. Phys.: Condens. Matter 21 364202





May addressed using several level of details/complexity



First approach (the simplest one) : Quasi-homogeneous or plug flow plasma model

Suitable for stationary glow discharges and plasma

Objective : To get a first idea on what is happening in trms of energy relaxation and chemistry

Though it light be not accurate quantitaively.

We can:

- build up very detailed CR models
- infer the major elementary processes
- setup simplified models

C. D. Scott et al. JTHT(1996), **10**(3), 10.2514/3.807 K. Hassouni et al. PSST **8**(1999), 494-512 K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp)



Plug flow plasma







Typical components involved in a quasi-homogeneous plasma model



Typical equations involved in quasi-homogeneous plasma model

-Relationship between power and electric field

-Determination of the plasma composition

-Estimation of the gas temperature

$$P_{Ohm} = \omega_p \left(\frac{\omega_p}{v_{qm}}\right) \frac{1}{\left(\omega / v_{qm}\right)^2 + 1} \frac{\varepsilon_0 E_0^2}{2}$$

-Determination of the eedf -Or the average electroln energy $f(e)=exp(-e/kT_e)$

$$\frac{\partial f(\varepsilon,t)}{\partial t} = -\frac{\partial J_E}{\partial \varepsilon} - \frac{\partial J_{el}}{\partial \varepsilon} - \frac{\partial J_{e-e}}{\partial \varepsilon} + Q_{in} = 0$$

$$\frac{\partial \widetilde{E}_{e}}{\partial t} = \left[PMW - \mathcal{Q}_{e^{-v}} - \mathcal{Q}_{e^{-t}} - \mathcal{Q}_{e^{-X}} \right] \frac{1}{\rho}$$

$$\frac{dY_s}{dt} = \frac{W_s}{\rho}$$

$$\frac{\partial \widetilde{E}}{\partial t} = \left[PMW - \frac{Q_{rad}}{Q_{rad}} - S_P \right] \frac{1}{\rho}$$

K. Hassouni et al. PSST 8(1999), 494-512

K. Hassouni et al. *Plasma Sources Sci. Technol.* (2001), **10**(1), 61

K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp)



Typical models for low pressure discharges with a local electron kinetics in the frame of the fluid approach

X Ions in thermal equilibrium with the neutrals :
$$T_i = Tg$$

X $E = E_{drift} + E_{thermal}$ with $E_{drift} >> E_{thermal}$ (at least in the sheath)
A Continuity equation for each neutral, ion and electron
 $a_{dt} + \nabla (n_s u_s) - W_s = 0$
An energy equation for electrons
Requires assumption on the cedf
 $a_{dt} = -\nabla (-2/3\kappa_s \nabla < \varepsilon_s > +5/3J_s < \varepsilon_s >) + e.J_s \cdot E - \sum_{coll} k_{coll} n_e n < \varepsilon_{th-coll} >$
A momentum equation for each charged species
 $a_{dt} - \nabla (p_s) = ep_s E - v_{s-qm} \rho_s u_s$
Simplification #1 : drift-diffusion transport
Suitable for cases with : $\lambda_{Debye} \approx d_{syst}$ et $\omega << \omega_s$
 $\frac{\partial \rho_s u_s}{\partial t} = 0$ (Requirfe the estimation of D_s et μ_s)
(advantage : no momentum equation)
Application : Fluid model for RF ; streamer propagation, ...

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Discharges with space charge separation : the drift-diffusion model. The example of CCRF discharges



Paris Nord

Typical simultion of reactive CCRF discharges

Paris Nord



Discharge dynamics – space-time distributions of electronmole fraction, electron-emperature and power density





Background gas composition

Acetylene conversion in Ar/C₂H₂ discharges 4% acetylene)



The precursor may be almost totally converted and the plasma is therefore generated in a gas composition that is strongly different from the feed gas one !

G. Tetard et al. PSST (2021), **30**, paper# 105015(22 pp) doi 10.1088/1361-6595/ac2a17 G. Tetard et al. Submitted to Plasma Process and Polymer - 2021

Transport and chemistry in low pressure plasmas No charge separation + fluid approach

Simplification #2 : Ambipolar diffusion

May be used when :

 $\lambda_{Debye} << d_{système} \quad | \quad$



Special case of 1 ion + 1 électron

$$-\mu_e n_e E_{amb} - D_e \nabla n_e = \mu_i n_i E_{amb} - D_i \nabla n_i$$
$$E_{amb} = \frac{D_i - D_e}{\mu_i + \mu_e} \frac{\nabla n_e}{n_e} \qquad \qquad J_i = -\frac{\mu_e D_i + \mu_i D_e}{\mu_i + \mu_e} \nabla n_i = -D_{amb} \nabla n_i$$

Advantage : Continuity equation = diffusion equation if no flow (no drift \rightarrow easier) $\frac{\partial n_i}{\partial t} + \nabla \mathbf{x} \left(-D_a \nabla n_i + \overset{\square \triangleright}{u} n_i \right) - W_i = 0$

Disadvantages : not so straightforward in the case of multicomponent plasmas (sevetral ions , negative ions, ...)



Multi-temperature ambipolar plasmas models



Results : space distributions of temperature and species (no current, no sheath and electroneutral plasma)-example of CH_4/H_2 microwave plasmas



K. Hassouni et al. J. Phys. D: Appl. Phys. 43 (2010) 153001 (45pp) F Silva et al 2009 J. Phys.: Condens. Matter 21 364202



G. Lombardi et al. PSST **14**(2005), 440-450, doi : 10.1088/0963-0252/14/3/005 G. Lombardi et al., J. Appl. Phys. **98**, 053303 (2005); <u>https://doi.org/10.1063/1.2034646</u>



Plasma-wave interaction: The example of microwave cavity generated plasmas



Plasma-wave interaction: The example of microwave cavity generated plasmas

2. 2D self consistent model

orbonne



Plasma-wave interaction. H₂ microwave plasma used for diamond deposition



EMILI 2021

Paris Nord

Effect of the feed gas composition on power coupling



S. Prasanna et al. PSST 26 (2017) 097001 (6pp)

The power coupling may substantially change even with a small change in the feed gas composition



Effect of buoyancy on power coupling



S. Prasanna et al. PSST 25 (2016) 045017 (10pp)

The power coupling may be significantly coupled to gas flow effects Here we show the fact that the power coupling is very sensitive to the buoyancy forces and the natural convection



Conclusion

- Reactivity in non equilibrium plasmas : Rich and diverse
- Non-equilibrium effects are also rich and diverse
- <u>Cannot be</u> treated without considering discharge and plasma physics, as well as energy relaxation (molecular and atomic physics)
- Usually strongly coupled sets of phenomena
- Usually Huge space <u>and</u> time stiffness : key consequences on both experiments and modeling
- I did not discuss some major open questions (among others ...) :
 - Plasma Surface Interaction and its feed back on the plasma behavior
 - Collisional data issues
 - Methodological issues (still not always straightforward)
 - Multiscale approaches











Thanks for listening

LSPM – CNRS-UPR3407 Université Sorbonne Paris Nord 99 Av J. B Clément 93430 Villetaneuse France

www.lspm.cnrs.fr

Tel: +33 1 49 40 34 54

Contacts : <u>khaled.hassouni@lspm.cnrs.fr</u> <u>Armelle.michau@lspm.cnrs.fr</u> <u>Swaminathan.prasanna@lspm.cnrs.fr</u>

